



OCT 2 1 2002

e Application of:

Shubneesh Batra et al.

Serial No.:

Filed:

July 10, 2001

For:

LOW TEMPERATURE REFLOW

METHOD FOR FILLING HIGH ASPECT RATIO CONTACTS

Assistant Commissioner for Patents Washington, D.C. 20231 Group Art Unit:

2825

Examiner:

Everhart, C.

Atty Docket: MCRO:199--3/FLE

95-0057.03

CERTIFICATE OF MAILING

37 C.F.R. 1.8

I hereby certify that this correspondence is being deposited with the U.S. Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231, on the date below:

October 15, 2002

Date

Tinsley

Sir:

AMENDMENT AND RESPONSE

Please amend the above-identified application, as follows:

IN THE CLAIMS

Please cancel claims 36, 45, 57 and 63, without prejudice.

Please amend claims 1, 30, 40, 48 and 60, as follows:

1 (Once Amended). A method of processing a semiconductor substrate, comprising the steps of: